

Table 1

Conditions	Amount of residual chlorine $\mu\text{m g/cm}^2$ $10^{15}\text{atoms/cm}^2$		After- corrosion	Symbols shown in Fig. 9
① Etching only	$0.92 \pm 0.06$	$16.0 \pm 1.0$	Large	○
② Downflow ashing using $\text{O}_2$ after ①	$0.89 \pm 0.06$	$15.5 \pm 1.0$	Large	●
③ Downflow ashing using $\text{O}_2 + \text{CF}_4$ after ①	$0.54 \pm 0.03$	$9.3 \pm 0.4$	Small	■
④ Downflow ashing using $\text{O}_2 + \text{H}_2\text{O}$ after ①	$0.23 \pm 0.03$	$4.0 \pm 0.5$	No	◇
⑤ Exposure to $\text{H}_2\text{O}$ after ② (30sec)	$0.51 \pm 0.02$	$8.7 \pm 0.3$	Small	▲
⑥ Exposure to $\text{H}_2\text{O}$ after ② (90sec)	$0.48 \pm 0.01$	$8.1 \pm 0.2$	Small	▲
⑦ Exposure to $\text{H}_2\text{O}$ after ② (180sec)	$0.45 \pm 0.04$	$7.6 \pm 0.7$	Small	▲
⑧ Downflow treatment using $\text{H}_2\text{O}$ after ② (30sec)	$0.28 \pm 0.01$	$4.7 \pm 0.2$	None	△
⑨ Downflow treatment using $\text{H}_2\text{O}$ after ② (90sec)	$0.15 \pm 0.00$	$2.5 \pm 0.0$	No	△
⑩ Downflow treatment using $\text{H}_2\text{O}$ after ② (180sec)	$0.11 \pm 0.01$	$1.9 \pm 0.1$	No	△
⑪ Downflow treatment using $\text{H}_2$ after ② (30sec)	$0.68 \pm 0.01$	$11.8 \pm 0.2$	Small	▼
⑫ Downflow treatment using $\text{H}_2\text{O}$ after ② (90sec)	$0.68 \pm 0.01$	$11.7 \pm 0.1$	Small	▼
⑬ Downflow treatment using $\text{H}_2$ after ② (180sec)	$0.64 \pm 0.01$	$11.1 \pm 0.2$	Small	▼

UNITED STATES PATENT AND TRADEMARK OFFICE  
**CERTIFICATE OF CORRECTION**

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INVENTOR(S) : Konno, et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 10-11, Table 1 should be deleted and substitute therefor the attached Table 1.

Signed and Sealed this  
Nineteenth Day of January, 1999

Attest:



Attesting Officer

*Acting Commissioner of Patents and Trademarks*